

AMENDMENTS TO THE SPECIFICATION:

Paragraph starting at line 20 of page 4 has been amended as follows:

The invention will be described next by way of an example with reference to Fig. 4 showing schematically a cable tray assembly 10 embodying this invention as having a movable stage portion, or a wafer table 15, placed on top of a drive stage 80. The drive stage 80 is a so-called XY stage of a known kind, adapted to be controllably moved two-dimensionally in a horizontal plane, having independently controllable means such as two electromagnetic motors ~~52 and 54~~ (not shown) for moving the stage 80 respectively in one specified linear horizontal direction (hereinafter referred to as the "longitudinal direction" and also as "the X-direction") and in the perpendicular horizontal direction (hereinafter referred to as the "transverse direction" and also as "the Y-direction"). Since the drive stage 80 itself is not a part of the present invention, device components for its motion are neither illustrated in Fig. 4 nor described in any detail herein.

The following paragraphs are added after line 15 of page 12:

--For example, the precision motion device shown in Figs. 4 and 5 may be incorporated for the motion of the reticle stage 116 shown in Fig. 1. Such a lithography system may be characterized as comprising an illumination source, an optical system, a reticle stage arranged to retain a reticle, a working stage, a stage motion controlling unit for controlling motion of this working stage in a specified longitudinal direction and a transverse direction which is perpendicular to the longitudinal direction, a wafer table placed on this working stage and arranged to retain a workpiece, a shaft extending in the transverse direction, a planar elongated member with one end portion extending in the longitudinal direction and the opposite end portion attached to and wound around the shaft, the elongated member being made of an elastic material and having a naturally arcuate sectional shape in the transverse direction, a plurality of conduits each attached to that end portion of the elongated member and to the wafer table at one end, and a shaft motion controlling system for controlling rotation and axial motion of the shaft in correlation with a motion of the

working stage by the stage motion controlling unit.

As another example, the precision motion device shown in Figs. 4 and 5 may be incorporated for the motion of the wafer stage 122 shown in Fig. 1. Such a lithography system may be characterized as comprising an illumination source, an optical system, a reticle stage arranged to retain a reticle, a stage motion controlling unit for controlling motion of this reticle stage in a specified longitudinal direction and a transverse direction which is perpendicular to the longitudinal direction, a shaft extending in the transverse direction, a planar elongated member with one end portion extending in the longitudinal direction and the opposite end portion attached to and wound around the shaft, the elongated member being made of an elastic material and having a naturally arcuate sectional shape in the transverse direction, a plurality of conduits each attached to that one end portion of the elongated member and to the wafer table at one end, a shaft motion controlling system for controlling rotation and axial motion of the shaft in correlation with a motion of the reticle stage by the stage motion controlling unit, a working stage, a wafer table placed on the working stage and arranged to retain a workpiece, and an enclosure that surrounds at least a portion of the working stage, the enclosure having a sealing surface.